Attorney Docket No.: YOR920030175US1

Westly Date: February 23, 2005

I hereby certify that this paper is being deposited on this date with the

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Patents, P.Q. Box/1450, Alexandria, VA 22313-1450

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Signature:

atent Application

Applicant(s): Allen et al.

Docket No.:

YOR920030175US1

Serial No.:

10/661,041

Filed:

September 12, 2003

Group:

2811

Examiner:

Cuong Quang Nguyen

Title:

Techniques for Patterning Features in Semiconductor Devices

INFORMATION DISCLOSURE STATEMENT

Commissioner of Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. §§1.56, 1.97 and 1.98, Applicant's attorney wishes to bring to the attention of the Patent and Trademark Office the following document listed on the accompanying PTO Form 1449. Pursuant to 37 CFR §1.97(e)(1), each of the identified references were cited in a European Search Report dated December 17, 2004 (i.e., not more than three months prior to the filing of this Information Disclosure Statement).

U.S. Patent(s)

- 1. U.S. Patent No. 5,753,418
- 2. U.S. Patent No. 6,009,888
- 3. U.S. Patent No. 6,316,167
- 4. U.S. Patent No. 6,387,798
- 5. U.S. Patent No. 6,514,86

Copies of each of the following listed items are enclosed:

Foreign Document(s)

6. EP 0 236 220 A1

Attorney Docket No.: YOR920030175US1

Other Document(s)

- 7. Celii et al., "Process Characterization for Tapered Contact Etch," J. Vac. Sci. Technol. B 19(5), American Vacuum Society, Pgs. 1845-1851 (Sept/Oct 2001).
- 8. Mahorowala et al., "Tunable Anti-Reflective Coatings with Built-In Hard Mask Properties Facilitating Thin Resist Processing," Proceedings of the SPIE, Vol. 4343, Pgs. 306-316 (2001).

In the event of non-payment or improper payment of a required fee, the Commissioner is authorized to charge or the credit **International Business Machines Corporation's Deposit Account**No. 50-0510 as required to correct the error.

The filing of this Information Disclosure Statement shall not be construed as a representation that a search has been made, or as an admission that the information cited is considered to be material to patentability or as a representation that no other material information exists.

Respectfully submitted,

Date: February 23, 2005

Michael J. Chang Attorney for Applicants Reg. No. 46,611 Ryan, Mason & Lewis, LLP 1300 Post Road, Suite 205 Fairfield, CT 06824 (203) 255-6560

FORM PTO-1449 (MODIFIED)

LIST OF PUBLICATIONS FOR **APPLICANT'S INFORMATION DISCLOSURE STATEMENT**

Applicant(s): Allen et al. Docket No.: YOR92003

YOR920030175US1

Serial No.: 10/661,041

September 12, 2003 Filing Date:

Group: 2811

		τ	J.S. PATENT DOCUMENTS		
EXAMINER					FILING DATE
NITIAL	DOCUMENT NO.	DATE	NAME	CLASS/SUBCLASS	IF APPROPRIATE
	5,753,418	05/19/98	Tsai et al.	430/313	
	6,009,888	01/04/00	Ye et al.	134/1.3	
	6,316,167	11/13/01	Angelopoulos et al.	430/313	
	6,387,798	05/14/02	Loke et al.	438/623	
	6,514,867	02/04/03	Hui et al.	438/713	
	<u> </u>	FOR	EIGN PATENT DOCUMENTS		
EXAMINER					TRANSLATION
NITIAL	DOCUMENT NO.	DATE	COUNTRY	CLASS/SUBCLASS	YES NO
	EP 0 236 220 A1	13/04/88	Europe		
			OTHER DOCUMENTS		
EXAMINER	REF NO. AUTHOR	TITLE DATE D	EDITINIENT DACES ETC		
INITIAL	REF NO. AUTHOR	C, IIILE, DATE, FI	ERTINENT PAGES, ETC.		
<u> </u>	Celii et al., "Process Characterization for Tapered Contact Etch," J. Vac. Sci. Technol. B 19(5), American Vacuum Society, Pgs. 1845-1851 (Sept/Oct 2001).				
	Mahorowala et al., "Tunable Anti-Reflective Coatings with Built-In Hard Mask Properties Facilitating Thin Resist Processing," Proceedings of the SPIE, Vol. 4343, Pgs. 306-316 (2001).				

Examiner	Date Considered

Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.